

Title (en)

Lithographic apparatus and device manufacturing method

Title (de)

Lithographischer Apparat und Verfahren zur Herstellung einer Vorrichtung

Title (fr)

Appareil lithographique et méthode de fabrication d'un dispositif

Publication

**EP 1482372 B1 20141008 (EN)**

Application

**EP 04253057 A 20040525**

Priority

- EP 04253057 A 20040525
- EP 03253420 A 20030530

Abstract (en)

[origin: EP1482372A1] The apparatus has a support structure supporting a patterning unit that patterns the projection beam according to a desired pattern. A projection system (PL) projects the patterned beam onto a target portion of the substrate. A liquid supply system fills the space between a final unit of the projection system and the substrate with an anti-reflective topcoat solution with a pH of less than seven. An independent claim is also included for a device manufacturing method.

IPC 8 full level

**G03F 7/20** (2006.01)

CPC (source: EP)

**G03F 7/70341** (2013.01); **G03F 7/70866** (2013.01); **G03F 7/70958** (2013.01)

Cited by

CN102262361A; EP1821338A4; CN106716255A; EP2073062A1; EP1791026A1; CN101055427A; US7903232B2; EP2267536A1; EP2267537A1; EP1528433A3; US8817227B2; WO2016020121A1; US10261422B2; US10534270B2; US7773195B2; US8456611B2; US8836912B2; US8953141B2; US9291914B2; WO2016096508A1; US10551748B2; US10859919B2; US8035799B2; US8913224B2; US10248034B2; US10527955B2; US8859188B2; US9164391B2; US9454088B2; US9772565B2; US10712675B2

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